Expitaxizing Untwinned PdCoO₂ Films by MBE

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Abstract

PdCoO₂ is a metallic delafossite material with a layered triangular structure and high in-plane conductivity, even higher than Pd metal itself. Thin film PdCoO₂ grown with Molecular Beam Epitaxy (MBE) on Al₂O₃ (0001) substrates currently has some structural defects that increase its resistivity. One of them is called "twinning," where the triangular structures go in two different directions 180 degrees opposite to each other. To solve the twinning problem, our Al₂O₃ substrates went through surface reconstruction from onemonolayer step height to two-monolayer step height before growth. However, after-growth characterizations such as Atomic Force Microscopy (AFM) and X-ray φ -scans still indicated twinning in our films grown on Al₂O₃ (0001) with two-monolayer step height. Alternatively, we have successfully achieved untwinned CuCrO₂ films on STO (111) substrates. Our future direction is to grow PdCoO₂ films on untwinned CuCrO₂ as buffer layers to eliminate twinning.

Introduction

Delafossite materials have a layered triangular structure with chemical formula *ABO*₂, mainly divided into insulating and metallic delafossites. PdCoO₂ [Fig. 1(a)] is one of the metallic delafossites with high in-plane conductivity, in room temperature comparable to aluminum and gold and even higher than pure palladium metal itself [1].



Figure 1. Structure information. (a) Crystal structure of PdCoO2 [2]. (b) Al2O3 (0001) substrate surface reconstruction description.

Growing PdCoO₂ thin films by Molecular Beam Epitaxy (MBE), we can control growth size based on the substrate size $(10 \times 10 \text{ mm})$ which is much larger than growing single crystals in the scale of only 1mm [3]; however, structural defects contribute to higher resistivity, one of them called "twinning"-PdCoO2 has triangular structures 180 degrees opposite from each other. This happens on Al₂O₃ (0001) substrates, where the crystal structure in each one-monolayer high steps face in a different direction alternately, resulting in PdCoO₂ growing on top of them having triangular structures in two different directions. In order to solve twinning, surface reconstruction was performed on the Al₂O₃ substrates, making the steps from one-monolayer high to two-monolayer high [Fig. 1(b)]. As the steps from the substrate are now all facing in the same direction, we hoped to grow PdCoO₂ with triangles in the same direction, thus achieving untwinned films.

Alternatively, PdCoO₂ films are expected to grow untwinned on an untwinned insulating CuCrO₂ buffer layer. CuCrO₂ can be grown on STO (111) substrate which does not have a twinning problem; however, PdCoO₂ fails to grow directly on top of STO (111), requiring an oxidizing pressure too high to reach.

Methods

Specially treated Al₂O₃ substrates were provided by our collaborators by annealing in high temperature. We used MBE for growth, monitored by Reflection High Energy Electron Diffraction (RHEED). Growth methods were absorption control growth and shuttering control growth. After-growth characterizations included X-ray Reflectivity (XRR), X-ray Diffraction (XRD), X-ray φ -scan, and Atomic Force Microscopy (AFM). φ -scan and AFM were especially important for twinning analysis. From φ scan, in the range of 360 degrees in-plane, three peaks were expected for the triangular structure; six peaks would indicate twinning in the film. From AFM, triangles oriented in two opposite directions would suggest twinning.

Results and Discussion

One of the specially treated Al₂O₃ substrates was scanned with AFM before growth [Fig. 3(a)]. Step height measured was around 0.449 nm, which is two monolayers as expected.

With same PdCoO₂ growth conditions on regular Al₂O₃ substrates, impurities appeared when growing on specially treated substrates. With absorption control growth, the impurities were palladium and Co₃O₄ [Fig. 2(a)]; with shuttering control growth, the impurities were PdO and Co₃O₄ [Fig. 2(b)]. This suggested that the surface energy of the Al₂O₃ substrate changed. New growth conditions are required to be found to attain pure PdCoO₂ films.



Figure 2. XRD data for PdCoO2. * = 006 peak of Al2O3 (0001) substrate. (a) Same absorption control growth condition on conventional and special Al2O3. (b) Same shuttering control growth condition on conventional and special Al2O3. (c) Best absorption control growth sample. (d) Best shuttering control growth sample.

AFM images were taken for different impurities. A typical AFM image showed big dots of around 30nm high and around 100nm wide [Fig. 3(b)], another showed small dots of around 8nm high and around 60nm wide [Fig. 3(c)]. After comparing with the corresponding XRD images, the former was recognized to be palladium impurity, and the latter was recognized to be PdO impurity. The impurities guide direction towards modifying growth conditions.



Figure 3. AFM images. (a) For specially treated Al2O3 substrate. (b) For PdCoO2 with Pd impurity. (c) For PdCoO2 with PdO impurity. (d) For PdCoO2 on special Al2O3. (e) For PdCoO2 on conventional Al2O3.

With improvement, we achieved almost pure PdCoO₂ films. For absorption control growth, the XRD image [Fig. 2(c)] contained strong peaks with clear fringes and no impurities. The AFM image [Fig. 3(d)] showed no dots suggesting pure films; however, there were three-fold strips on the surface, which is different from triangles we usually see for PdCoO₂ grown on regular Al₂O₃ substrates [Fig. 3(e)]. It was difficult to read whether there was twinning from the three-fold strips instead of oriented triangles. For shuttering control growth, PdCoO₂ film quality was also good, where there were only very weak Pd and Co₃O₄ impurity peaks shown on XRD [Fig. 2(d)].

X-ray φ -scans were conducted on the high-quality PdCoO₂ films grown on special Al₂O₃ substrates. From the results [Fig. 4(a)], there were still six peaks instead of three with equal intensity, indicating twinning. With the alternative solution of growing PdCoO₂ on an untwinned buffer layer of CuCrO₂, we chose to find the optimal growth condition for CuCrO₂ films first. We achieved pure CuCrO₂ films on STO (111) substrate as proved by XRD [Fig. 4(b)]. What is especially exciting is that by φ -scan [Fig. 4(c)] there were only three CuCrO₂ peaks, confirming we have successfully achieved untwinned CuCrO₂ films. It is promising that we will be able to attain untwinned PdCoO₂ films in the future.



Figure 4. X-ray data. (a) φ -scan for PdCoO2 on special Al2O3. (b) XRD for CuCrO2. (c) φ -scan for CuCrO2.

Conclusions and Future Work

Growth conditions for PdCoO₂ films changed after surface reconstruction was performed on the Al₂O₃ (0001) substrates to two-monolayer step heights. As seeking for the best growth conditions, we were able to distinguish various impurity phases in AFM. Finally, we have almost achieved pure PdCoO₂ films, but the twinning problem still exists.

Our future directions will be growing PdCoO₂ on untwinned CuCrO₂ buffer layer to solve the twinning problem. There is hope as we have successfully grown untwinned CuCrO₂ films on STO (111) substrates.

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